

**LITHOGRAPHIC APPARATUS, LEVEL SENSOR, METHOD OF
INSPECTION, DEVICE MANUFACTURING METHOD, AND DEVICE
MANUFACTURED THEREBY**

ABSTRACT

A level sensor for a lithographic projection apparatus according to one embodiment of the invention includes a light source, a first reflector, a second reflector and a detector. The first reflector is positioned to direct light from the light source towards a wafer surface, and the second reflector is positioned to direct light reflected from the wafer surface to the detector. The first and second reflectors are selected to incur a minimal process dependent apparent surface depression.